

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 6,968,531 B2  
APPLICATION NO. : 10/073246  
DATED : November 22, 2005  
INVENTOR(S) : Yoshimasa Iiduka et al.

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 9, Line 56, delete "where" and insert -- wherein -- therefor.  
Column 9, Line 57, after "optical" insert -- proximity --.  
Column 10, Line 2, after "data" insert -- at --.  
Column 10, Line 5, delete "exposed" and insert -- exposure -- therefor.  
Column 10, Line 8, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 10, after second occurrence of "exposure" insert -- pattern --.  
Column 10, Line 11, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 17, after "data" insert -- is expected to be less than that of the minus objective pattern data and the minus pattern data --.  
Column 10, Line 18, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 21, delete "exposed" and insert -- expected -- therefor.  
Column 10, Line 22, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 24, after "bitmapped" insert -- pattern --.  
Column 10, Line 26, delete "th" and insert -- the -- therefor.  
Column 10, Line 31, delete "where" and insert -- wherein -- therefor.  
Column 10, Line 45, after "data" insert -- at --.  
Column 10, Line 51, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 53, after "divided exposure" insert -- pattern --.  
Column 10, Line 54, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 62, after "minus" insert -- objective --.  
Column 10, Line 63, delete "optical" and insert -- optional -- therefor.  
Column 10, Line 65, after "of the" insert -- minus objective pattern data and the minus pattern data is expected to be less than that of the --.  
Column 10, Line 66, delete "optical" and insert -- optional -- therefor.  
Column 11, Line 7, delete "side" and insert -- sides --.  
Column 11, Line 15, after "data" insert -- at --.  
Column 11, Line 17, delete "apparatus" and insert -- method -- therefor.  
Column 11, Lines 19-20, after "data" delete ", to generate corrected exposure pattern data, the apparatus" and insert -- and exposes a substrate in accordance with bitmapped pattern data, the method -- therefor.  
Column 11, Line 24, after "exposure" insert -- pattern --.  
Column 12, Line 3, after "minus" insert -- objective --.  
Column 12, Line 3, after "wherein" insert -- an area corresponding to the minus pattern data is included in an area corresponding to --.  
Column 12, Line 14, delete "side" and insert -- sides -- therefor.  
Column 12, Line 16, delete "claim 7" and insert -- claim 10 -- therefor.

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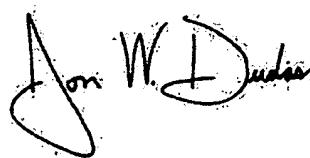
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Column 12, Line 22, after "data" insert -- at --.

Signed and Sealed this  
Second Day of January, 2007



JON W. DUDAS  
*Director of the United States Patent and Trademark Office*